

KOREAN PATENT ABSTRACTS(KR)

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Applicant:

LG Cable Co. Ltd.

Inventor:

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Priority:

NONE

** This application is considered to be withdrawn before its publication date.

Title of Invention

METHOD OF REMOVING OH⁻ RADICAL IN DEPOSITION LAYER WITH DEHYDRATION PROCESS IN MCVD

(57) Abstract:

A method of removing moisture from a deposition layer with the use of a dehydration process in MCVD, comprising the steps of: generating soot and depositing the soot on a quartz tube by heating the quartz tube at a temperature of 1600°C or below with flowing reaction gas and oxygen gas into the quartz tube and moving a heat source; removing hydroxyl groups existing in the generated soot and moisture existing in the tube by flowing dehydration gas into the quartz tube and moving the heat source so that the quartz tube keeps 1200°C; and sintering and vitrifying the soot particles deposited on the tube by heating the quartz tube at a temperature over 1700°C with moving the heat source.